

A CHEMICAL VAPOR DEPOSITION (CVD) APPARATUS USABLE IN THE  
MANUFACTURE OF SUPERCONDUCTING CONDUCTORS

5 ABSTRACT OF INVENTION

A chemical vapor deposition (CVD) apparatus including a reactor, at least one substrate heater, at least one precursor supply system, at least one precursor injector, and at least one precursor composition monitor. The precursor supply system includes at least one precursor source, at least one a delivery mechanism including at least one assist vehicle, at least one vaporizer for vaporizing a precursor provided by at least the at least one precursor source, and at least one vehicle for transporting at least the vaporized precursor from the precursor supply to the precursor injector of the CVD apparatus.